



RADIATION TESTS OF OPTOELECTRONIC DEVICES AND IMAGE SENSORS: ADVICE AND PITFALLS

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GENERIC RETURN OF EXPERIENCE AND ADVICES ON SEE TESTING

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Is this requirement can be apply in space project today ?

“No part sensitive to SEE”

INTRODUCTION

/// Today can we comply with such requirement : “No part sensitive to SEE” ?

- / Today All Digital and Analog VLSI are more or less sensitive to SEE
- / not possible to be compliant to such requirement except with a very specific radiation hardened device : huge effort & very expensive device

/// Solution : Analyses to demonstrate that EEE Device Sensitive to SEE can be used if :

- / SEE **Impact and Rate** are acceptable at equipment or system level : Availability / Reliability / FMEA
- / Specific technics are applied to remove/mitigate effects

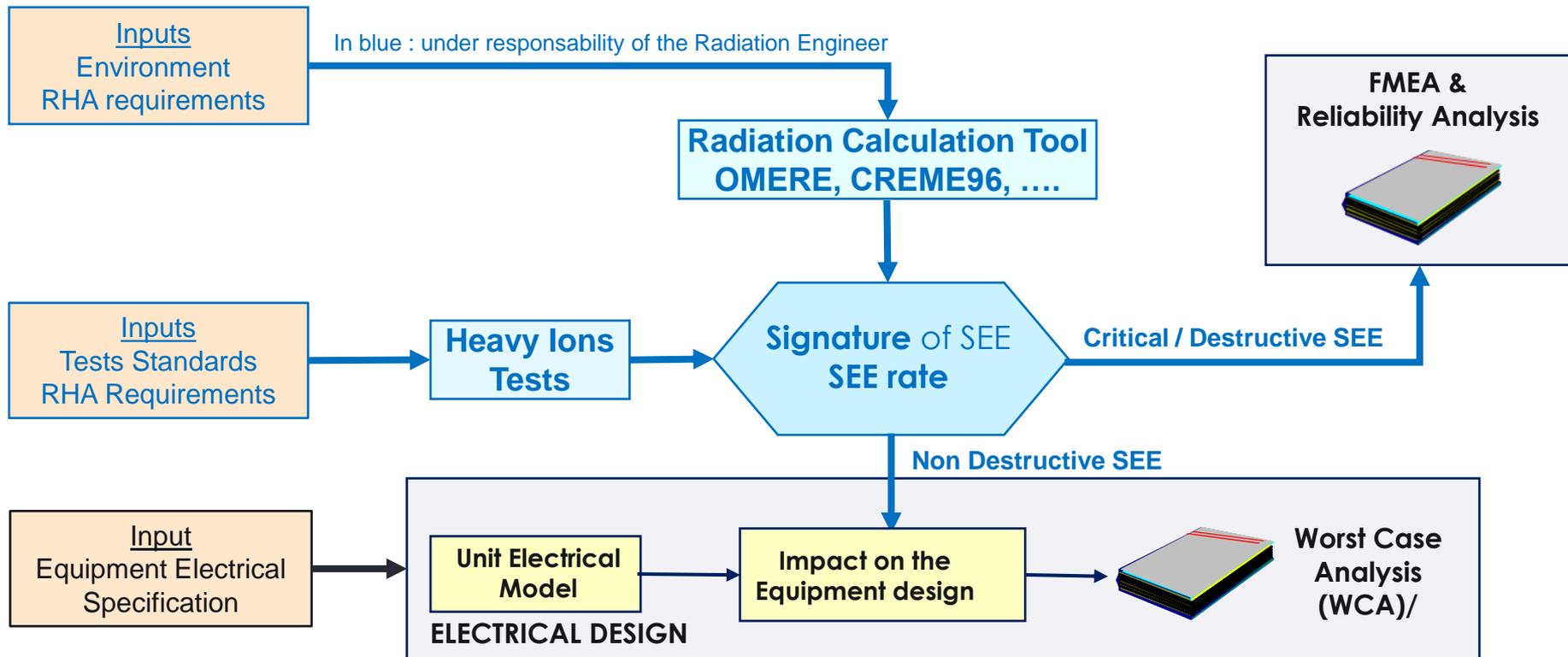
But we need RELIABLE SEE DATA to perform such analyses

What are reliable SEE Test Data ?

PROPRIETARY INFORMATION

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SEE RADIATION HARDNESS PROCESS IN SPACE PROJECT



In black : Checked during unit PDR/CDR – under responsibility of Designer & RAMS Engineers

TRACEABILITY

/// Traceability provided in the Test Report

- / Sample Serial Numbers, Date Code and Mask set
- / Pictures of package, die and die marking, Die size in mm
- / Device technology : e.g. FinFET TSMC 7 nm
- / μ cross-section : Depth of active region and dead layers

either measured or from Manufacturer's data

/// SEE is done only during Evaluation Phase if

- / Flight traceability is identical to evaluation samples traceability
- / Mask, technology shall be verified
- / Part Change Notice (PCN) : to follow any change

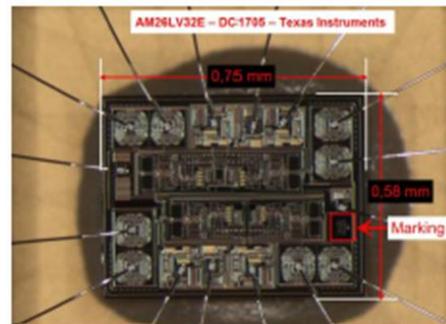
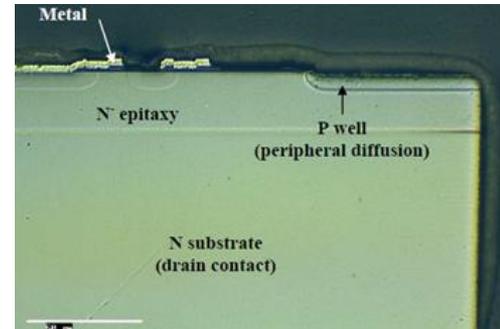


Figure 2: Internal overall view



Figure 3: Die marking



If data traceability is not known, Flight Mask shall be tested

HOW TO REPRODUCE GCR ENVIRONMENT ?

/// Impossible to reproduce the GCR space environment

! Very complex environment composed of high energy ions

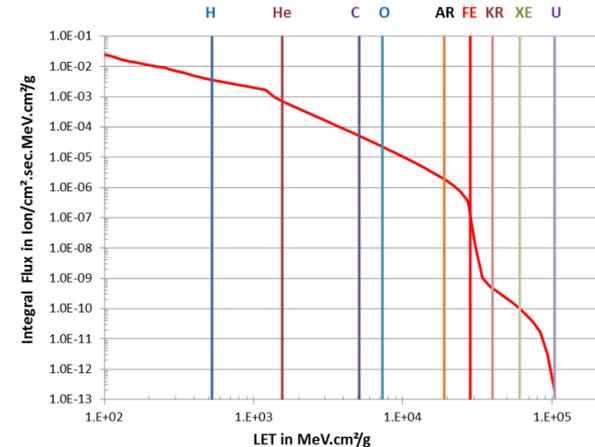
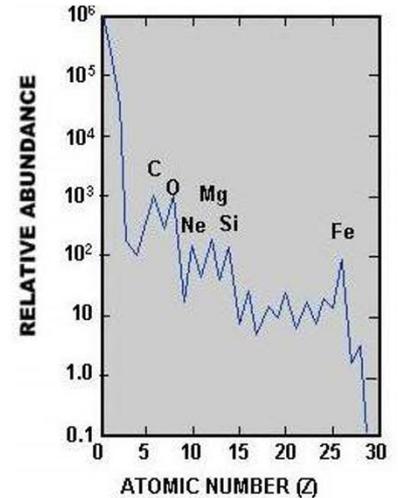
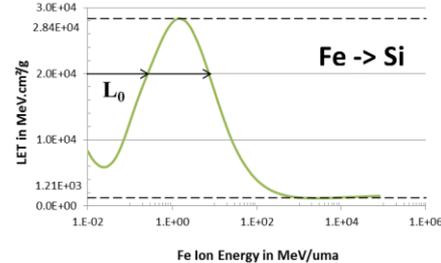
/// The solution :

- ! Linear Energy Transfer in Material : e.g. LET(Si)
- ! High energy may produce the same effect than low Energy
- ! Low energy ground facility can be used

/// Environment defined by LET spectrum

/// Cyclotron are used to reproduce GCR environment

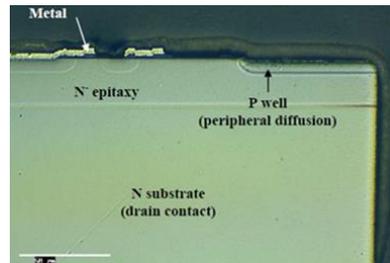
- ! Facility usually available in research context (University,..)
- ! UCL : 9 MeV/amu is operated in vacuum
- ! RADEF : from 9 to 22 MeV/amu is operated in vacuum or in air



SELECTION OF THE CYCLOTRON

/// Need to know the different layers of the DUT

! µsection and observation (SEM) in order to measure the thickness of layers



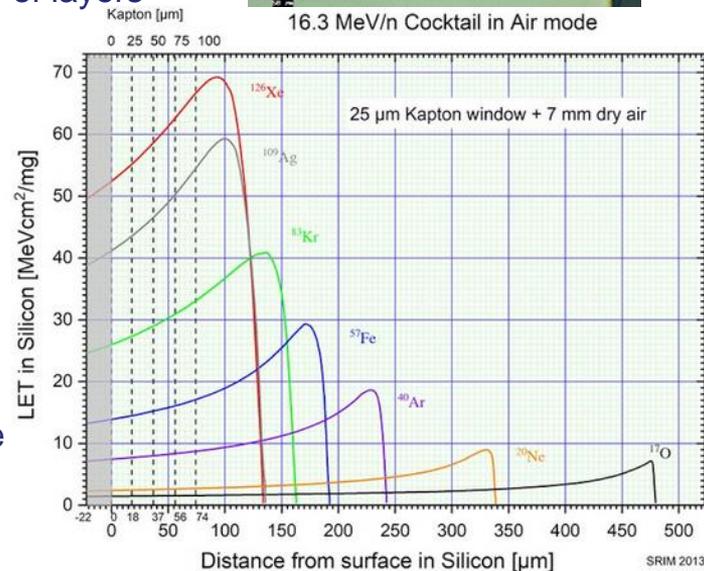
/// Bragg peak shall be beyond the active area of the DUT

! Beam may quickly stopped when going through several layers

- Kapton, Air, ...
- dead layer of device : metal, oxyde (in frontside) or Silicon (backside)

! OMERE (SRIM) used to calculate LET behind several layer in Si

! DUT may be prepared to remove some layers and comply with the requirements

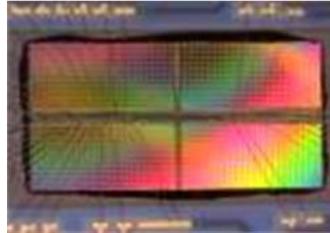


Need to prepare samples for Heavy Ions Testing

SAMPLE PREPARATION

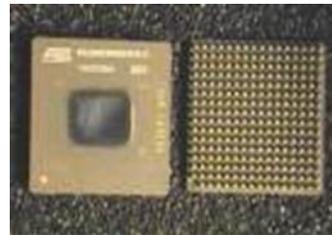
/// Different solutions for delidding operation :

- Removing by mechanical or chemical operations the front side of the package when the die is top side in the package.



- Thinning the device by the back side by polishing or milling when the die is mounted back side in the package

77.3 µm	74.5 µm	72.0 µm	72.5 µm	74.7 µm	77.3 µm
77.9 µm	73.4 µm	72.1 µm	71.8 µm	73.9 µm	77.0 µm
75.8 µm	72.1 µm	70.1 µm	70.3 µm	73.2 µm	75.8 µm
75.7 µm	71.6 µm	69.6 µm	70.2 µm	72.1 µm	75.6 µm
77.2 µm	74.4 µm	73.0 µm	73.2 µm	75.2 µm	76.8 µm
76.1 µm	74.6 µm	73.7 µm	73.9 µm	76.5 µm	76.9 µm



TEST CONDITIONS

/// !\ Data shall cover all the different applications used in Flight

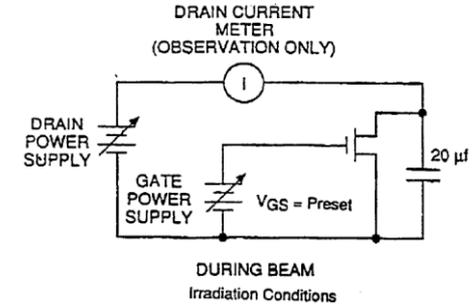
- ! Test to be done in the worst case condition for several use cases
- ! Test as you fly if only one application case

/// Test conditions applied during the test

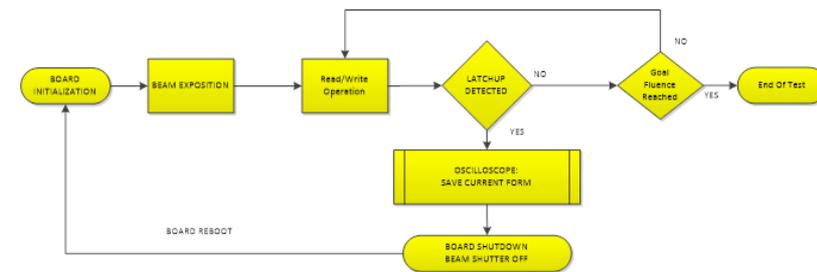
- ! Input voltages and/or input signal (waveform, pattern....) & output conditions
- ! Power supply Bias conditions
- ! Frequency & Data Sampling Rate
- ! T° : requirement may be different for NDSEE (Non Destructive) & DSEE (Destructive)
 - e.g; : SEL at upper T° used in application
- ! Number of bits, channels, IPs, memory size tested

/// Test Setup

- ! Information on how SEE are acquired during Test
- ! Test sequences described in a flowchart



MOSFET set-up from EIA/JESD57



FLUENCE AND FLUX

/// 2 criteria to stop the run

1. Fluence to 10^7 ions/cm² : to be used to identify all type of events, included rare event, at higher LET
2. Only when all type events are known : run may be stopped when 100 events for each type of events are reached (without going up to 10^7 ions/cm²)

!/\ Do not use only “100 events reached criteria” to perform your test

/// Flux

/ High Risk if flux is too high :

- To miss event : set up is not enough quick to detect and record all events
- To create events that will not appear in space :
 - e.g. : MBU in memory word due to two or more ion hits in the same word between two different read cycle

/ Selection of the flux : verification that same results are obtained with low and high flux before to use high flux

RULES FOR DATA POST PROCESSING

/// To consider only as one event all impacts induced by a single heavy ion hit

/// Classification with following criteria based on :

- / level of criticality of the impact : Destructive (Reliability), critical at system level (FMEA), impact on the Availability (outage)
- / end-user analysis : expected impact on the mission & Mitigation Technic put in place
 - e.g. : If an EDAC is used on a memory : event that can be corrected (SBU) and event not correctable (MBU)
- / Signature of the event
 - Number of bits flipped in same time (NB they shall be counted only as one event)
 - /! the number of flip bits can not be more than the total number of ions received
 - Signature linked to the architecture of the DUT : column, row, page,.....
 - For analog event : by duration or amplitude
 -

SIGNATURE OF EVENT & DEVICE CROSS SECTION VERSUS LET

/// For each type of SEE :

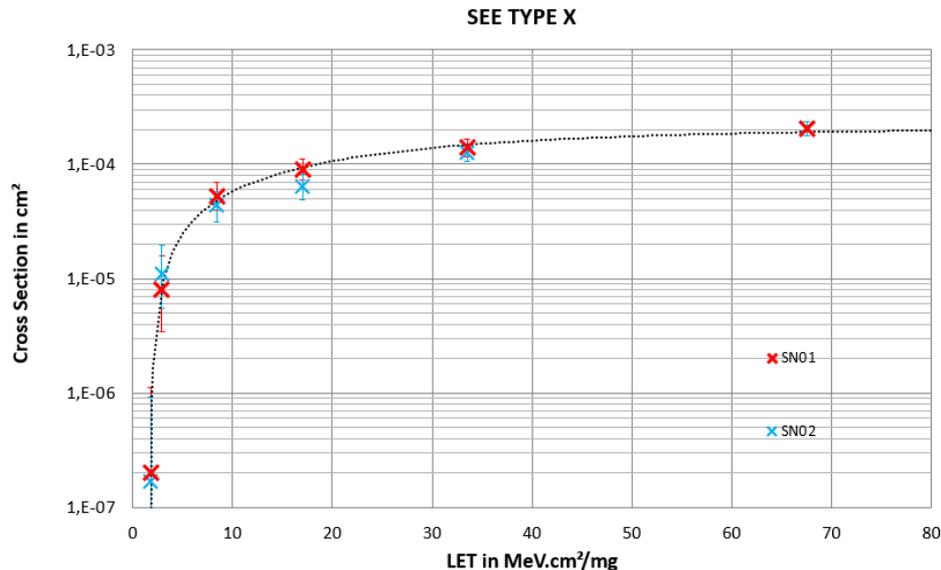
/ Detailed description of the signature of the event

NOK : « SEFI »

OK : Loss of functionality detected by a current consumption increase. This event can be recovered only with a Power OFF/ON cycle

/ Detailed device cross section versus LET

- at least 5 different values of LET used to determine carefully
 - LETth
 - Knee shape
 - Saturated cross section



WHAT ABOUT THIRD PARTY TEST DATA ?

/// Third party data (published paper, public database, manufacturer) shall be analysed carefully

/ **TRACEABILITY** : detailed information available ? Identical to the Flight Lot ?

/ **TEST COVERAGE** : Electrical conditions used during the test cover my application ?

/ **EVENT SIGNATURE** Are all signature of events detailed in test report ?

/ **CALCULATION RATE** : Are full device cross section versus LET available for each type of event ?

- At least 5 ions used during test
- At least 2 samples with same behaviour for NDSE
- At least 3 samples with same behaviour for DSEE

/ Test fully compliant with ESCC Basic Specification No. 25100 Issue 2 ?

/// If data available are not enough reliable, this data can be used as screening test but a new test shall be done

In any case of doubt, a new test shall be done



Radiation Tests of Optoelectronic Devices and Image Sensors: Advice and Pitfalls

Matthieu Beaumel

#

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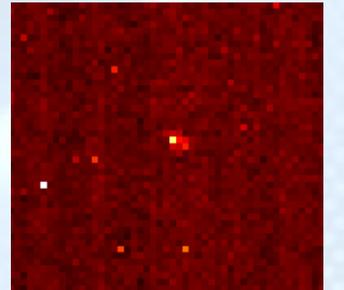
A M B I T I O N S

DISPLACEMENT DAMAGE DOSE TESTS ON CMOS IMAGE SENSORS



Displacement Damage Dose Effects

- As described this morning, Displacement Damage Dose (DDD) creates vacancies and more complex defects in the silicon lattice, which act as Shockley-Read-Hall generation centers in the pixel photodiode depletion regions.
- Large defects will create “hot pixels” or “spikes” in the image sensor area, characterized by dark current values several times higher than the main pixel population.
- Parameters most affected by DDD:
 - Dark Current
 - Dark Current Non-Uniformity (DCNU)
 - Parasitic Storage Node Leakage (PSNL) on global shutter CIS
 - Conversion factor for high irradiation levels ($>1E12$ 60 MeV protons/cm²)
 - Quantum efficiency for high irradiation levels ($>1E12$ 60 MeV protons/cm²)
- Dark Current Random Telegraph Signal (RTS) will also appear, especially in pixels with high dark current increase
 - Blinking pixels alternating between 2 or more dark current values (metastable states)



Non-Ionizing Energy Loss (NIEL) Scaling

- Displacement Damage Dose scales linearly with the Non-Ionizing Energy Loss (NIEL) of incident particles.
- The degradation scales linearly with DDD, especially mean dark current increase.

$$DDD = \Phi \times NIEL(E)$$

MeV/g ↑ #/cm² ↑ MeV.cm²/g

$$\Delta DC = k_d \times DDD = K_{dark} \times V_{dep} \times DDD$$

e-/s ↑ k_d ↑ Exp. Result ↑ Universal Damage Factor (**Srouf 2000**)
 $\approx 1E-4 \text{ (e-/s) / (MeV/g) / } \mu\text{m}^3$

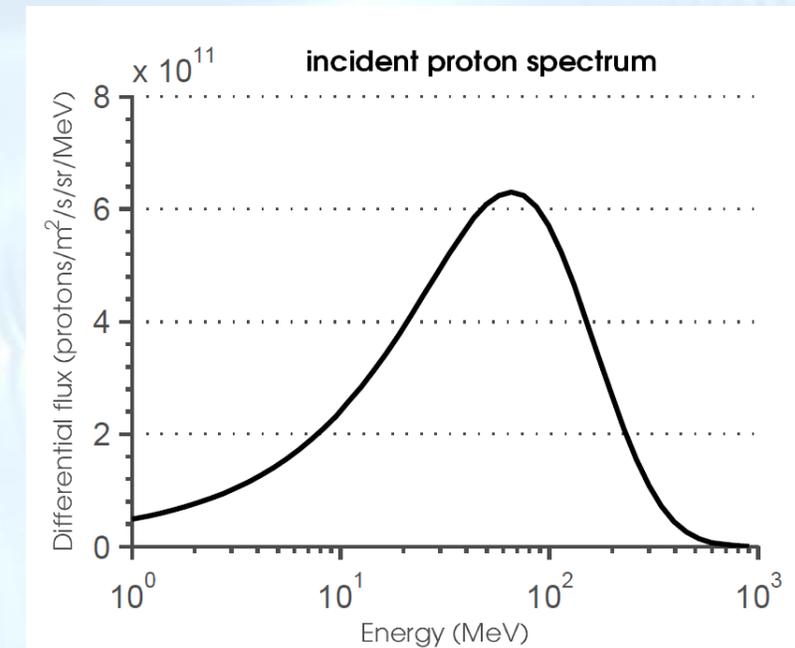
μm^3

- Displacement Damage Dose is therefore often expressed by an equivalent fluence of monoenergetic particles, which would cause the same amount of damage.
- **/!** As discussed by C. Inguibert this morning, this holds true for hadrons (protons and neutrons) in silicon. For the same DDD, electrons cause significantly less degradation.
- **/!** Strong Electric fields will increase dark current generation through Poole-Frenkel effect and trap-assisted tunneling. Discrepancies are observed with "Universal Damage Factor" for fields >1E7 V/m
- Theoretical NIEL tables in silicon can be obtained from several sources (**G.P. Summers 1993, I. Jun 2003, Konobeyev 1992...**), with little differences in values compared to typical experimental accuracy.

Displacement Damage Dose Irradiations

- Readily available sources :
 - Protons from cyclotrons (typical energy: 10 to 200 MeV)
 - Neutrons from Deuterium-Tritium generators (energy: 14 MeV)
 - Fission neutrons from nuclear reactors (energy spectrum)
- **/!** Lower energy beams (e.g. 10 MeV) are often generated using beam degraders from higher energy beams.
 - This increases energy deposition straggling (variation in energy deposition in the CIS from particle to particle)
 - Lower energy beams also have a higher energy loss when crossing materials (front window of the CIS)
 - All these factors affect negatively the accuracy of the deposited DDD
- Recommended proton beam energy : **50 – 60 MeV**.
 - Range of 50 MeV protons in aluminum : 16 mm
 - Peak energy of Van Allen belt trapped protons through typical satellite shielding on LEO orbits
- **/!** Protons will also deposit Total Ionizing Dose
- Biasing conditions during irradiation: **unbiased** (no significant influence)

Incident proton spectrum incident on a star tracker image sensor on a 850 km LEO orbit



Displacement Damage Dose Test Levels

Earth observation mission:

LEO 850 km, 98° inclination

10 years lifetime

DDD: 3E10 50 MeV protons/cm²

Geosynchronous telecom mission:

GEO 36000 km + Electrical Orbit Raising phase

15 years lifetime

DDD: 2E10 50 MeV protons/cm²

Telecom constellation mission:

LEO 1200 km, 55° inclination

10.5 years lifetime

DDD: 1E11 50 MeV protons/cm²

Europa Clipper mission:

Fly-bys over Jupiter's moon Europa

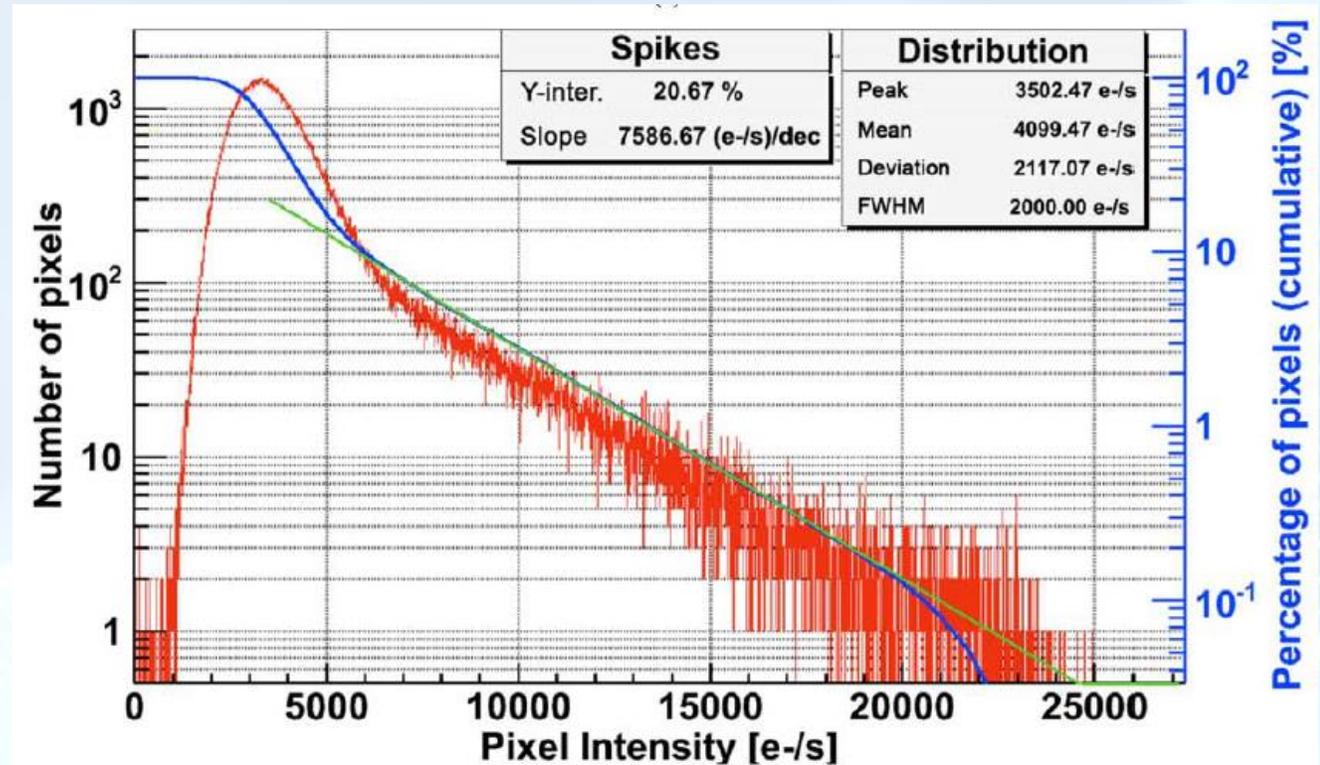
DDD: 1E10 50 MeV protons/cm²

/! Do not forget to add margins to cover part-to-part and lot-to-lot variations, up to x2

Dark Current Distribution Characterization

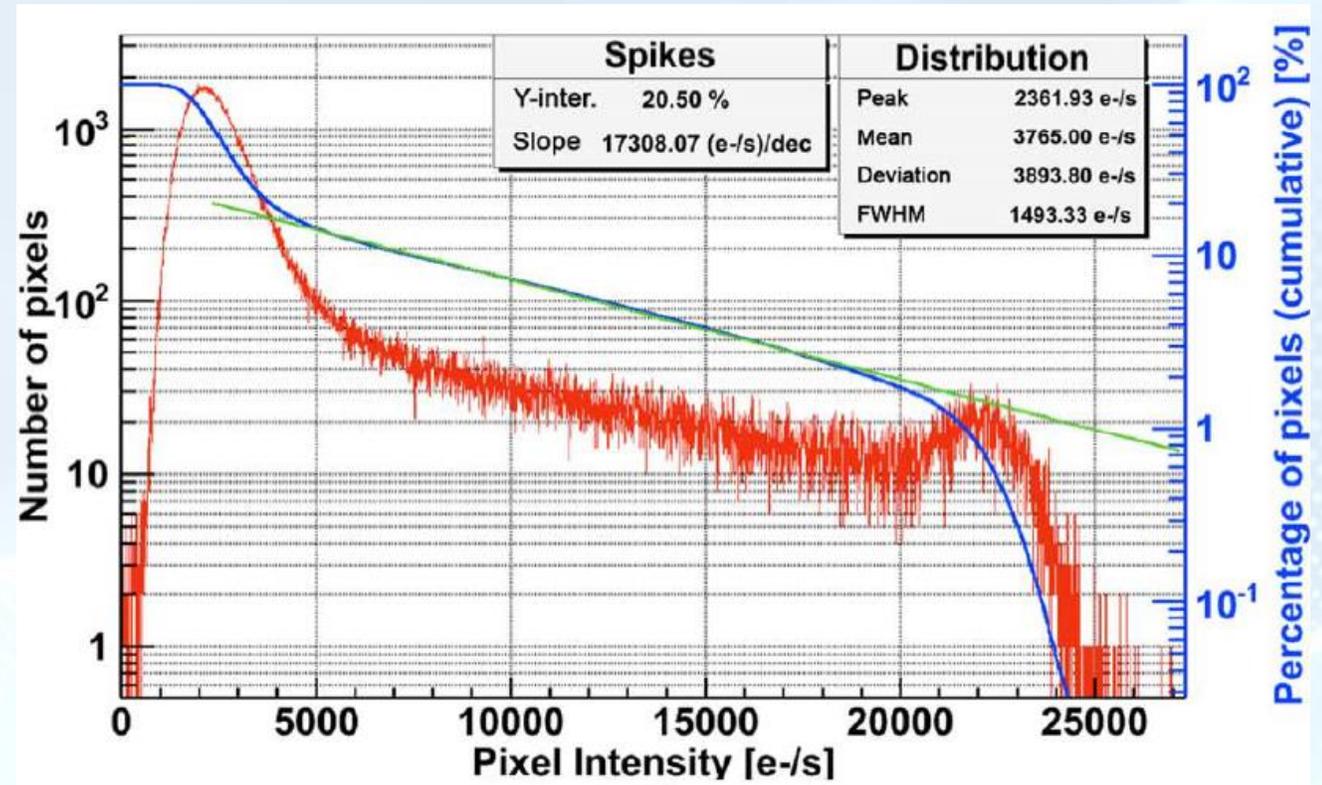
- The analysis of dark current increase distribution is the most straightforward way to assess DDD effects to the CIS.
- Mean dark current increase will be proportional to DDD.
- Hot pixels / spikes will appear as exponential-like distribution tail.
- This distribution tail appears as a straight line when plotted on a **lin-log** scale.
- This allows the extraction of the number of hot pixels (proportional to fluence) and the slope of the exponential distribution.
- This distribution has been extensively studied and can also be estimated from the photodiode depletion volume (**C. Virmontois 2012**, etc).

1 Mpixel 3T CIS irradiated with $\sim 2E11$ 62 MeV protons/cm²



Dark Current Distribution Characterization

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!/ Beware of saturation effects when estimating mean dark current increase

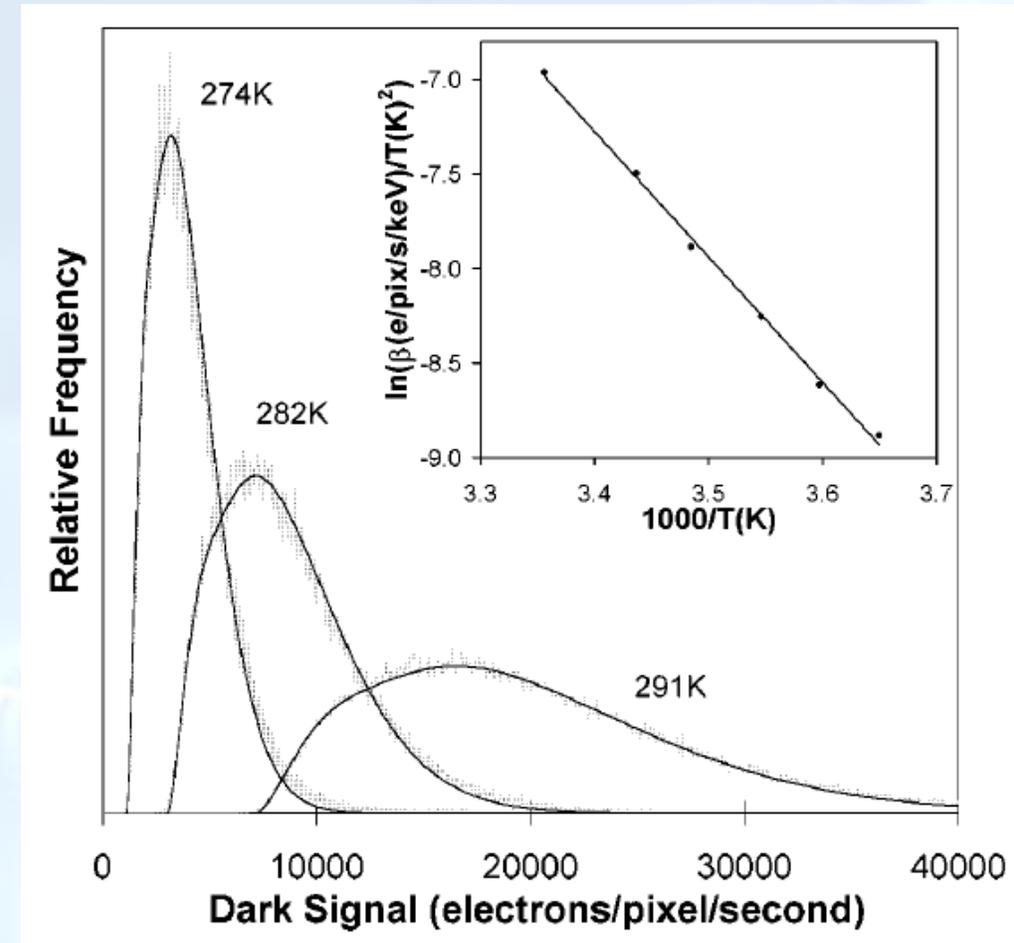
Temperature effects

- Dark current is exponentially dependent on temperature (Arrhenius-like law).

$$DC \propto \exp(-E_a/k_bT)$$

- **⚠** Accurate knowledge of the CIS temperature during dark current measurements is therefore critical.
- Activation energy of the dark current increase law should be assessed by performing measurements at several temperatures.
 - This allows dark current increase to be determined for a range of operating temperatures
 - Typical activation energy of DDD defects in silicon: **0.63 – 0.82 eV**
 - Corresponding dark current doubling temperature near room temperature : **7°C – 9°C**

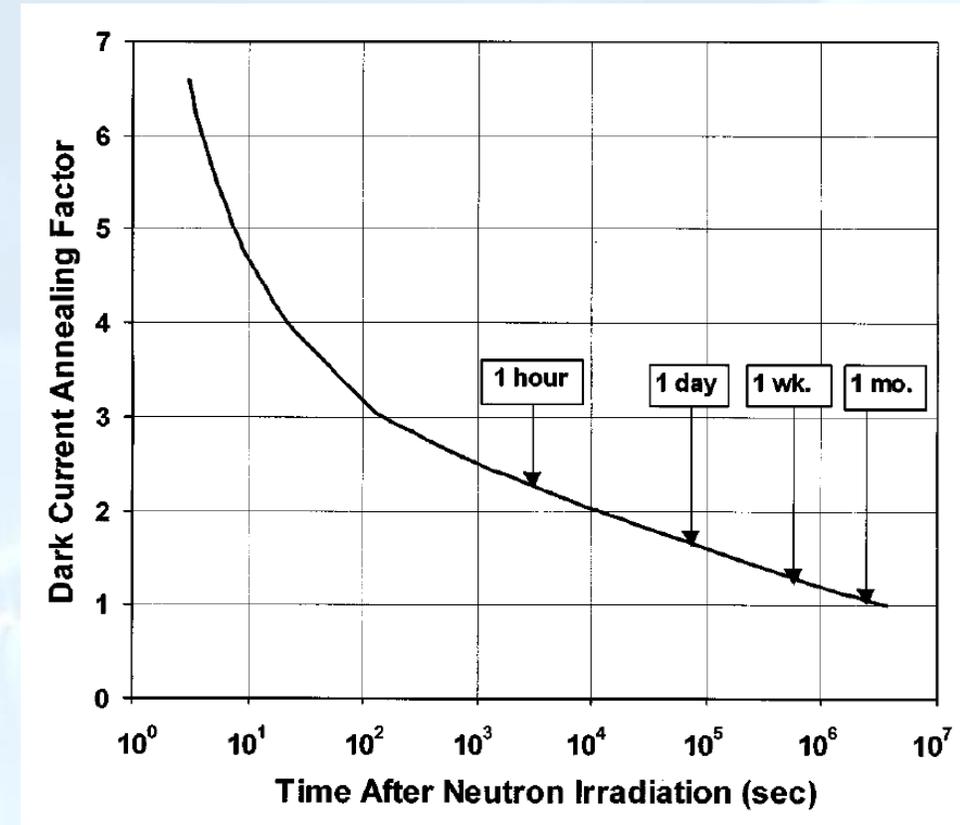
⚠ Field enhancement effects will lower the activation energy: all pixels may not have the same dark current activation energy



Dark current dependence on temperature, CCD irradiated with $3.4E10$ 60 MeV protons/cm² (M. Robbins 2000)

Displacement Damage Annealing

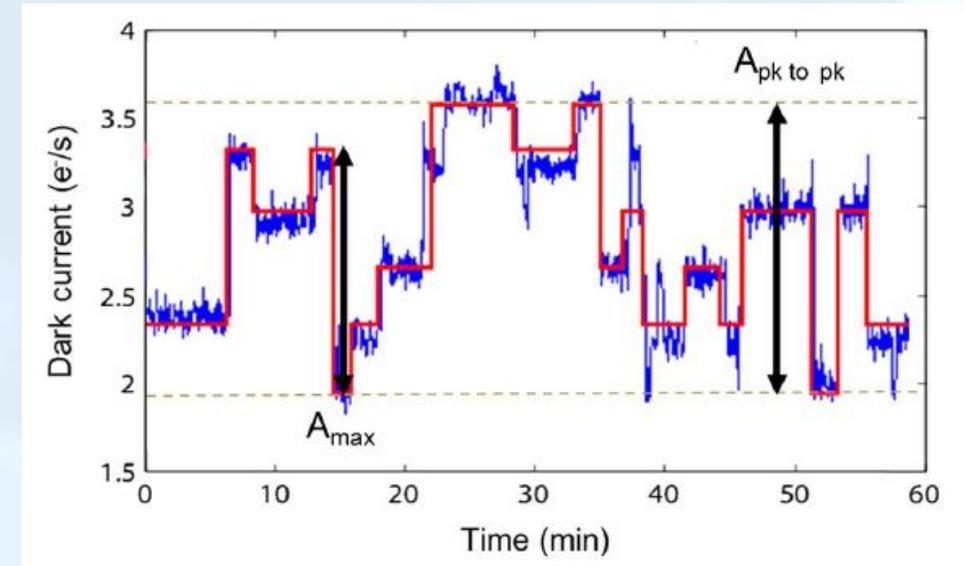
- Dark current-induced displacement damage first anneals very quickly at room temperature, then reaches a pseudo-plateau.
- **/!** Depending on the intended application, dark current measurements can be not very representative if performed straight after the irradiation.
- In any case, the time duration between the irradiation and the measurements must be carefully recorded
- Typical time for measurements: 3 weeks after irradiation.
- Depending on the intended application temperature, a high temperature annealing step after irradiation can be interesting, as temperatures above 70°C greatly anneal DDD-induced dark current. Typical annealing time at high temperature : 1 week.
- **/!** CIS intended to be used in low temperature applications (typically <-50°C) must be irradiated at the application temperature, otherwise room-temperature annealing effects may cause an underestimation of the degradation at the intended temperature.



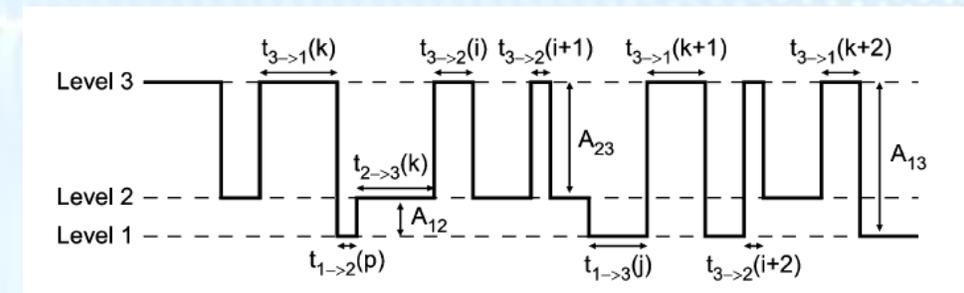
Annealing factor from Srour 2000, normalized to 1000h

Random Telegraph Signal (RTS)

- Random Telegraph Signal (RTS) pixels exhibit blinking behaviour: their dark current values will switch between 2 or more “semi-stable” states.
- Hot pixels with high dark current are the most likely to exhibit RTS, but weakly damaged pixels can also be subject to RTS.
- **!/** Depending on the intended application, it can be a matter of lesser interest or critical for performance
 - On average, RTS will not change the dark current distribution or the associated shot noise
 - However, RTS will greatly impair the ability to perform pixelwise dark current correction through dark current mapping
- **!/** Characterizing RTS requires long test sequences (recording images during several hours and a few seconds period)
- Standard technique for detection and characterization of RTS pixels : **Edge detection technique (V. Goiffon 2009)**
- This allows to characterize for each RTS pixel
 - Number of levels
 - Transition amplitudes
 - Inter-transition periods



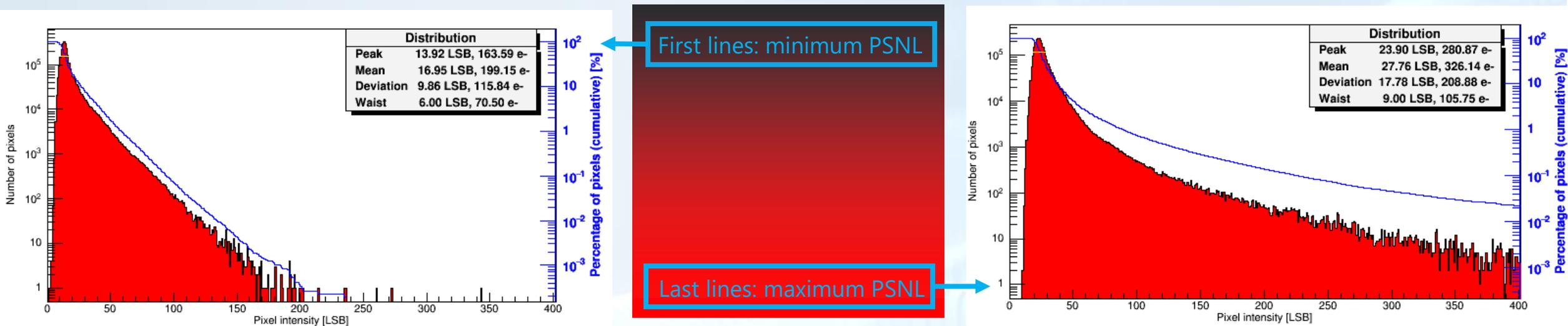
Example of multi-level RTS from C. Virmontois 2013



RTS parameters extraction from V. Goiffon 2009

Parasitic Storage Node Leakage (PSNL)

- PSNL is the equivalent of dark current in the memory node on a Global Shutter CIS (accumulated between the end of integration time and the readout of the line).
- **/!** On large Global Shutter CIS, DDD-induced PSNL can be a dominant contributor.



Global shutter CIS irradiated to
 $\sim 4E11$ 1 MeV n/cm²

- CIS performing double sampling / correlated double sampling in the voltage domain are expected to be less sensitive to such effects, but this is not always the case...
- In such cases, perform measurements with different integration times / line readout times to be able to selectively cancel DC or PSNL contribution.



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TOTAL IONIZING DOSE TESTS ON CMOS IMAGE SENSORS



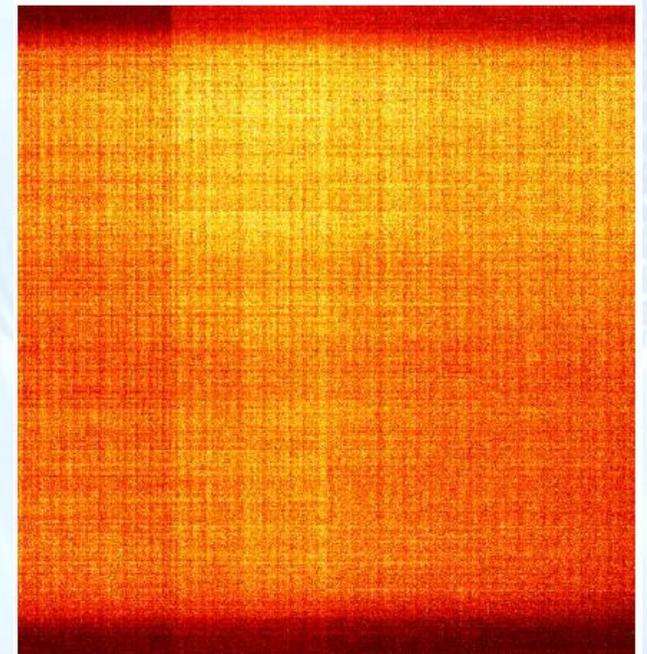
Total Ionizing Dose Effects

- Total Ionizing Dose creates charges trapped in the CIS oxides and interfaces traps.
- Interface traps in contact with the pixel photodiode depletion region will cause the increase of dark current.
- The CIS Read-Out Integrated Circuit (ROIC) electrical characteristics will degrade.
- Parameters most affected by TID:
 - Dark Current
 - Dark Current Non-Uniformity (DCNU)
 - Parasitic Storage Node Leakage (PSNL) on global shutter CIS
 - Fixed Pattern Noise (FPN)
 - Charge Transfer Efficiency / Lag in pinned photodiode pixels
 - Full Well Capacity (FWC) in pinned photodiode pixels
 - Readout noise
 - Conversion factor
 - Quantum Efficiency
- As for DDD, Dark Current Random Telegraph Signal (RTS) will also appear.

Total Ionizing Dose Irradiation

- Readily available sources:
 - Cobalt-60 (1.33, 1.25 MeV gamma rays)
 - X-Rays tubes (typically from 10 to 100 keV)
- Cobalt-60 is usually preferred over X-rays because of several advantages:
 - Very high penetration depth in materials (half value layer in Aluminum: 6.8 cm), good resulting homogeneity
 - Higher charge yield (more representative of electrons in orbit)
 - However, much higher dose rates can be achieved with X-rays
- **/!** Be wary of TID equilibrium issues with Cobalt-60:
 - Co-60 gammas create Compton electrons in silicon with ~ 1 MeV energy
 - Such electrons have a range of ~ 1 mm and can “escape” the silicon if no or very thin surrounding materials are present
 - This can create a strong overestimation of the deposited TID (factor ~ 2 ...)
 - **With Co-60, always irradiate packaged dice**
- Biasing conditions during irradiation: **biased** (worst-case for ROIC) and **unbiased** (not required for PPD, but can be worst-case for newer structures).
- No enhanced low dose rate sensitivity (ELDRS) reported in CIS.

2 Mpixel CIS dark current map at 30 krad after Co-60 irradiation



Total Ionizing Dose Test Levels

Earth observation mission:

LEO 850 km, 98° inclination
10 years lifetime
TID: 4 krad

Geosynchronous telecom mission:

GEO 36000 km + Electrical Orbit Raising phase
15 years lifetime
TID: 6 krad

Telecom constellation mission:

LEO 1200 km, 55° inclination
10.5 years lifetime
TID: 20 krad

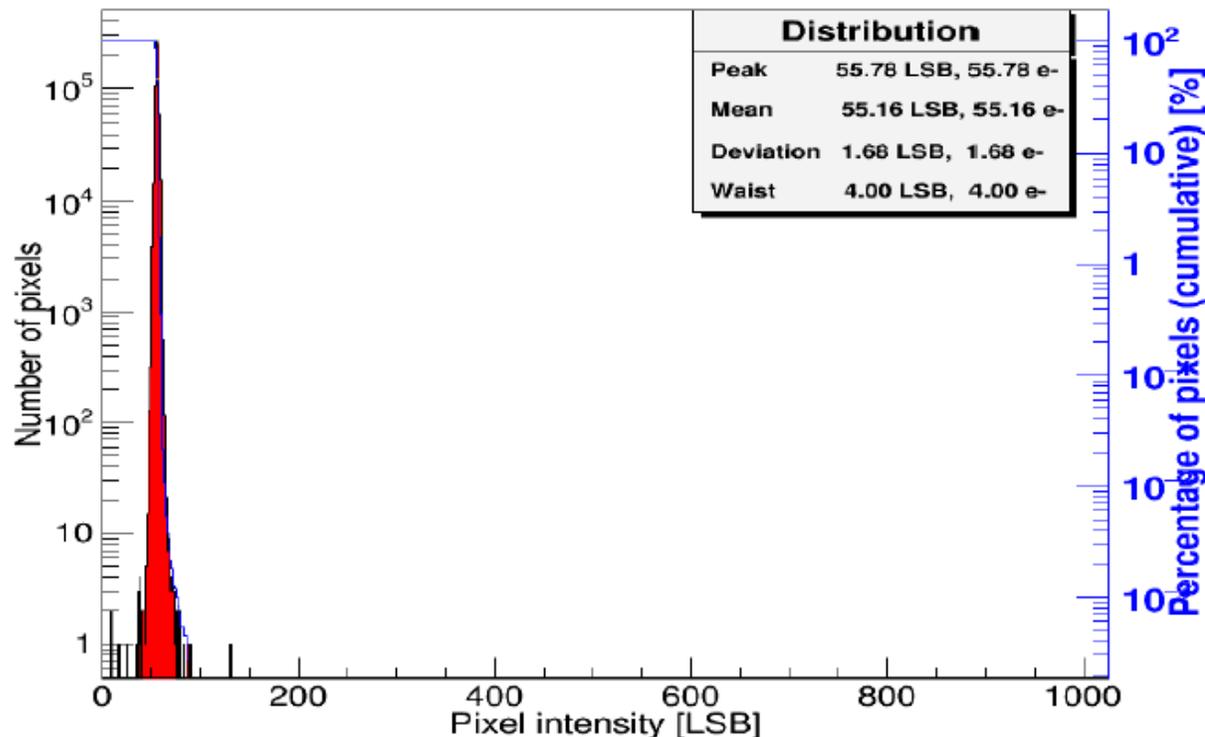
Europa Clipper mission:

Fly-bys over Jupiter's moon Europa
TID: 50 krad

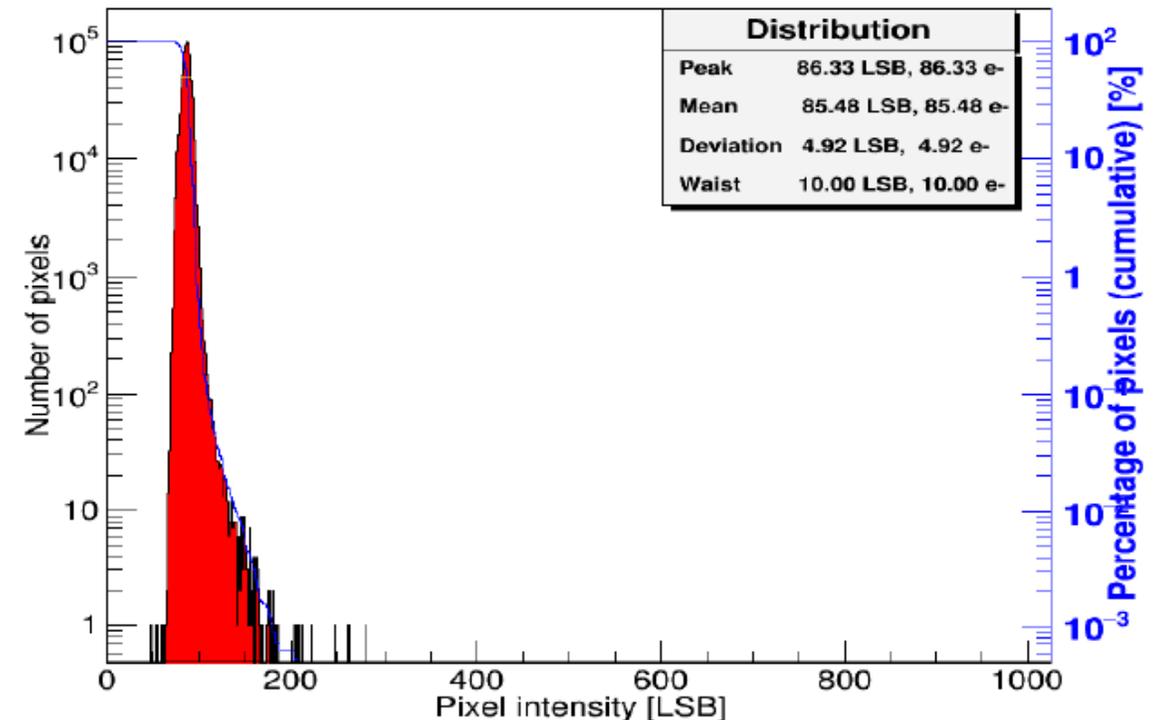
/! Do not forget to add margins to cover part-to-part and lot-to-lot variations, up to x2

Dark Current Distribution Characterization

- In contrast to DDD damage, TID will induce a more uniform increase of dark current.
- **⚠** TID effects can be non-linear as higher levels are reached:
- **Do not extrapolate TID degradation at higher doses.**
- **Be very careful when interpolating TID degradation between large TID levels steps.**



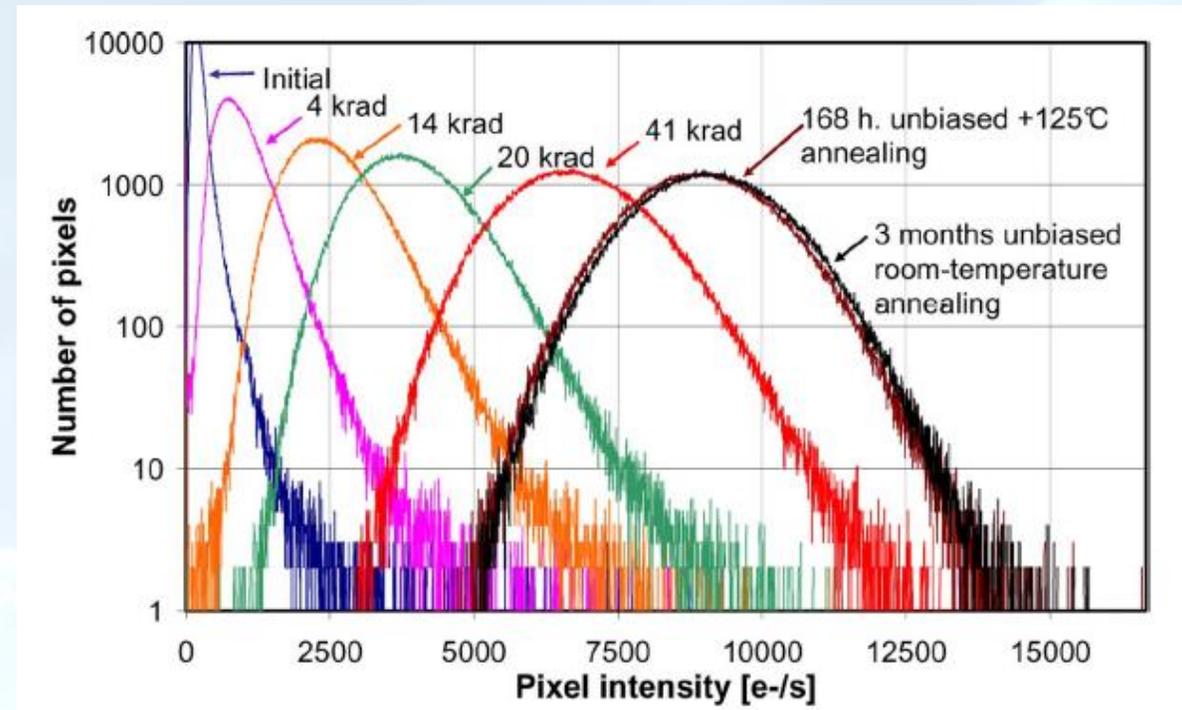
Initial 2 Mpixel CIS dark current distribution



2 Mpixel CIS dark current distribution at 30 krad

Total Ionizing Dose Annealing

- **/!** In some cases, reverse annealing (increase of degradation at the end of irradiation) has been observed on CIS.
- TID irradiation standards such as ESCC 22900 or MIL-STD-883 TM1019 mandate accelerated annealing (100°C during one week) at the end of the irradiation to characterize these effects.
- It is a good practice to perform this annealing step
- Of course, it can also reduce the degradation through the de-trapping of oxide charges



Reverse annealing on 1Mpixel 3T CIS



20 avenue Descartes
94451 Limeil-Brévannes Cedex
France

www.sodern.com



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